

WEST Search History

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DATE: Tuesday, January 24, 2006

<u>Hide?</u>	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
		<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surfactant same hydrophilic and ((multiple or plural\$3) with polish\$3)	2
<input type="checkbox"/>	L18	L18 and octanol	5
<input type="checkbox"/>	L17	L17 and alcohol and clean\$	55
<input type="checkbox"/>	L15	L15 and alcohol	65
<input type="checkbox"/>	L14	L14 and alkohol	0
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) and ((post CMP) or (after CMP) or (after polish\$3)) and surface and surfactant and hydrophilic and ((multiple or plural\$3) with polish\$3)	
<input type="checkbox"/>	L13	L13 and alkohol	90
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic and ((multiple or plural\$3) with polish\$3)	
<input type="checkbox"/>	L12	L12 and alkohol	2
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic same ((multiple or plural\$3) with polish\$3)	
<input type="checkbox"/>	L11	L11 and alkohol	0
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic same ((multiple or plural\$3) with polish\$3)	
<input type="checkbox"/>	L10	L10 and alkohol	2
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic same ((multiple or plural\$3) with polish\$3)	
<input type="checkbox"/>	L9	L9 and alcohol	13
		((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic	
<input type="checkbox"/>	L8	L8 and alcohol	21
		((wafer or semiconductor or substrate) same (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic	
<input type="checkbox"/>	L7	L7 and alcohol	13
		((wafer or semiconductor or substrate) same (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO. _{sub.2} ')) same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic	
<input type="checkbox"/>	L6	L6 and alcohol	18
		<i>DB=USPT; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L5	L5 and alcohol	7
<input type="checkbox"/>	L4	L4 and alcohol	0

- L3 6444583.pn. 1
DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ
((wafer or semiconductor or substrate) with (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2'))
- L2 same ((post CMP) or (after CMP) or (after polish\$3)) same surface same surfactant same hydrophilic 17
((wafer or semiconductor or substrate) with (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2'))
- L1 same (((post CMP) or (after CMP) or (after polish\$3)) with surface with surfactant with hydrophilic) 0

END OF SEARCH HISTORY